

Canon

**FPA-5500iZa**

|                         |                    |
|-------------------------|--------------------|
| <b>1. ID No</b>         |                    |
| <b>2. Description</b>   | <b>Scanner</b>     |
| <b>3. Manufacturer</b>  | <b>Canon</b>       |
| <b>4. Model</b>         | <b>FPA-5500iZa</b> |
| <b>5. Wafer Size</b>    | <b>300mm</b>       |
| <b>6. Vintage</b>       | <b>Mar. 2006</b>   |
| <b>7. Serial Number</b> |                    |
| <b>8. Location</b>      |                    |

The equipment being quoted is used, and is being sold “AS-IS, WHERE IS” basis unless otherwise agreed. This equipment data may contain typographical errors and we do not warrant the completeness or accuracy of the information contained herein. Any reliance you place on any information on this equipment data is strictly and completely at your own risk. Any offer by you to purchase of the equipment described in this equipment data shall be subject to our standard terms and conditions of sale.

- Configuration & Specification

| Description                  | Specification                                          | Remarks |
|------------------------------|--------------------------------------------------------|---------|
| Reticle                      |                                                        |         |
| Size                         | □6" t=0.25"                                            |         |
| Surface                      | 2 Layers Cr, 3 Layers Cr, HT                           |         |
| Pellicle                     | Only pattern surfaces can be installed                 |         |
| Wafer Size                   | 300mm                                                  |         |
| Wafer chuck type             | 12 Inch Pin chuck                                      |         |
| Exposure System              |                                                        |         |
| Projection Lens              | UL61-II                                                |         |
| Magnification                | 1 : 4                                                  |         |
| NA                           | Auto Variable (0.57~0.45 / 0.01 Resolution)            |         |
| Screen Size                  | 26 x 33mm                                              |         |
| Exposure Light               | i Line (365nm)                                         |         |
| Optical Component protection | CDA Substitution                                       |         |
| Illumination optical system  |                                                        |         |
| Light source                 | IZ Light system III                                    |         |
| Manufacturer/Model           | 4.5Kw Ultra high-pressure mercury lamp                 |         |
| Light Mode                   | Ushio Inc. / SUV-4500CIL                               |         |
| Exposure Control             | Choose from normal lighting                            |         |
| Masking Blade                | Cumulative exposure method                             |         |
| Optical Component protection | Aperture Range: □0.4mm ~ X:26mm, Y:33mm                |         |
| Lamp position adjustment     | CDA & N2 Substitution                                  |         |
|                              | 3-axis automatic adjustment(X-axis / Y-axis / Z- axis) |         |

- Configuration & Specification

| Description              | Specification                              | Remarks |
|--------------------------|--------------------------------------------|---------|
| Main Body                |                                            |         |
| MMI                      | Touch panel color LCD (eConsole)           |         |
| Body structure           | 5500 body                                  |         |
| Mount                    | Hybrid (LM + Air)                          |         |
| Chamber                  | Model : CD162 / SN : CD16261R060           |         |
| Signal Tower             | None                                       |         |
| Logger                   | None                                       |         |
| Console type             | e-console                                  |         |
| Console position         | Side (Booth2 L)                            |         |
| Focus System             |                                            |         |
| Focus / Leveling         |                                            |         |
| Detection method         | Optical focus method                       |         |
| Drive method             | Wafer Stage drive                          |         |
| Focus calibration        |                                            |         |
| Detection Method ALFC    | Image processing method by TTR             |         |
| Others                   |                                            |         |
| Change in pressure focus | Automatic Correction                       |         |
| Change in exposure focus | Automatic Correction                       |         |
| AA System                |                                            |         |
| Reticle alignment        |                                            |         |
| Alignment method         | Matching with the R-standard mark by FRAS  |         |
| Detection Method         | Image processing method                    |         |
| Alignment light          | i Line(365nm)Transparent lighting          |         |
| Reticle holding method   | R/S upper reticle holder adsorption method |         |

- Configuration & Specification

| Description                                | Specification                                                    | Remarks |
|--------------------------------------------|------------------------------------------------------------------|---------|
| OFF AXIS Wafer alignment system            |                                                                  |         |
| Alignment light                            | 590±60nm (Wavelength switching mode)                             |         |
| Detection Method                           | Image processing method                                          |         |
| Measuring mode                             | AGA method                                                       |         |
| Base line detection                        | Matching with the Stage standard mark                            |         |
| Mechanical pre-alignment                   | Circumference non-contact method                                 |         |
| TV pre-alignment                           | TV Image processing method                                       |         |
| Stage system                               |                                                                  |         |
| Wafer Stage                                | FLAT II modification stage                                       |         |
|                                            | 6-axis measurement of laser interferometer                       |         |
| Exposure range of movement                 | XY : ±165mm                                                      |         |
| Compatible with laser wavelength variation | Wavelength change correction function using barometer (standard) |         |
| Laser wavelength correction                | Real -time correction by wavelength tracker                      |         |
| Wafer transport system                     |                                                                  |         |
| Wafer Transport                            |                                                                  |         |
| Inline                                     | Left to right (Standard)                                         |         |
|                                            | Front side / Open Cassette                                       |         |
| Chuck maintenance unit                     | Equipment front-side access                                      |         |
| Auto feeder type                           | FR type – Relay unit (Reject carrier 5 Slot)                     |         |

- Configuration & Specification

| Description                               | Specification                              | Remarks |
|-------------------------------------------|--------------------------------------------|---------|
| Reticle system                            |                                            |         |
| Reticle Changer                           |                                            |         |
| Number of Reticle storage                 | 14ea (Standard) Nikon type                 |         |
| Expansion library                         |                                            |         |
| Number of Reticle storage                 | 15ea (Total 29ea)                          |         |
| Pellicle foreign object inspection device | Yes                                        |         |
| Reticle barcode reader                    | 2D                                         |         |
| Cassette barcode reader                   | Yes (3 of 9 barcode)                       |         |
| Others                                    |                                            |         |
| Failure parts                             | None                                       |         |
| Missing Parts                             | None                                       |         |
|                                           | HDD is not included                        |         |
| Construction                              | Main Body, Relay Unit                      |         |
| QC Data                                   | Please refer to the attached QC data sheet |         |

[illegible]







